Press Release





Nanonex Delivers Advanced Nanoimprint Tool NX-B200 to Columbia University

Princeton NJ, Feb. 12, 2007: Nanonex Corporation, the inventor and world's leading provider in nanoimprint lithography solutions with the longest history, announces the delivery of a Nanonex NX-B200 system to Columbia University in New York, NY.

The Nanonex NX-B200 installed at Columbia is a compact, cost-effective and versatile sub-10 nm resolution nanoimprint tool, utilizing Nanonex's patented Air Cushion PressTM technology to provide unsurpassed uniformity and yield over the entire substrate. The NX-B200 also incorporates a fully flexible Smart Sample Holder that accommodates any size of substrate or mask up to the maximum capability including arbitrary shaped geometries.

The NX-B200, a part of central facility of Columbia's micro/nanofabrication laboratory and NSF NSEC Center, was purchased by the Shalom Wind group, whose research focus is experimental studies of single molecule transistors, carbon nanotube synthesis and electronic device integration, and biomolecular-scale nanofabrication. Nanonex is proud to support the leading edge research of Dr. Wind and his colleagues at Columbia.

About Nanonex Corporation

Nanonex is the inventor of "nanoimprint lithography", the world's first nanoimprint lithography company, and the world's leading provider of nanoimprint solutions that include equipment, masks, resists and processes. Nanonex's patented and proprietary nanoimprint lithography (NIL) solutions and Air-Cushion PressTM can manufacture 3D nanostructures with sub-5 nm resolution, large-area uniformity, accurate overlay alignment, high throughput, and low cost. Nanonex NIL solutions have been adopted by a broad spectrum of industry applications, such as optical devices, data storage, displays, light emitting diodes, semiconductor ICs, biotech, chemical synthesis, and advanced materials. Nanonex has over 100 customers and an installed base of more than 40 tools world-wide. Visit www.nanonex.com for additional information.